

Abstract of the Disclosure

Since it is possible to exhaust air from a first peripheral region  $\alpha$  around a substrate undergoing processing and further exhaust air from a second  
5 peripheral region  $\beta$  between the first peripheral region and substrate, it is possible to reduce effects of the current of air on a developing solution on a substrate and to cause the developing solution used in development processing to act on the exposed resist on the substrate  
10 properly.